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L14 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN

Accession Number

2002:429483 HCAPLUS Full Text

Document Number

137:14561

Title

Metal foil laminated integrated circuit package

Author/Inventor

McLellan, Neil; Fan, Chun Ho; Tsang, Kwok Cheung; Lau, Pik Ling

Patent Assignee/Corporate Source

Asat Ltd., Hong Kong

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002068378	A1	20020606	US 2000-730440	20001205 <
US 6429048	B2	20020806		

Abstract

The present invention relates generally to packaging for integrated circuit (IC) devices, and in particular to a method of fabricating a metal foil laminated package for ball grid arrays. A method of fabricating an integrated circuit package for ball grid arrays comprises the following steps: laminating layers of fiberglass prepreg and Cu foil to a Cu plate to create a 3-layer laminated carrier; patterning and etching contact pads for input/output and a power/ground ring; applying a solder mask and plating up the contact pads and the ring with a wire bondable metal surface; forming window openings for receiving semiconductor dies; attaching the dies within the windows, wire bonding the dies to the contact pads and the ring, encapsulating the dies, attaching solder balls to the contact pads to create finished packages and singulating the finished packages into individual packages; and attaching the Cu plate portion of each of the individual packages to Cu plate heat spreader.

Concept or Classification

76-14 (Electric Phenomena)

Supplementary Terms

metal foil integrated circuit package

Controlled or Index Terms

Electronic packaging process
(for a **metal foil laminated** integrated circuit package)

Laser ablation

(for etching of metal foil laminated

integrated circuit package)

Electric contacts

Lamination

(for metal foil laminated integrated

circuit package)

Electronic packages

Integrated circuits

Printed circuit boards

Semiconductor devices

(metal foil laminated integrated circuit

package)

Glass fibers, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(metal foil laminated integrated circuit

package containing)

Etching

```
Soldering
         (of metal foil laminated integrated
         circuit package)
      Interconnections, electric
         (via; for metal foil laminated integrated
         circuit package)
      12670-46-1
      RL: TEM (Technical or engineered material use); USES (Uses)
         (contact pad; metal foil laminated
         integrated circuit package containing)
      7440-50-8 , Copper , uses
      RL: TEM (Technical or engineered material use); USES (Uses)
         (foil; metal foil laminated
         integrated circuit package containing)
National Patent Classification
      438106000
International Patent Classification
     ICM H01L021-44
      ICS H01L021-48 ; H01L021-50
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STIC-EIC 2800

L19 ANSWER 2 OF 8 HCAPLUS COPYRIGHT 2004 ACS n STN

Accession Number

2001:152416 HCAPLUS Full Text

Document Number

134:187108

Title

Processes for manufacturing flexible wiring boards and the resulting flexible wiring boards

Author/Inventor

Kurita, Hideyuki; Watanabe, Masanao

Patent Assignee/Corporate Source

Sony Chemicals Corporation, Japan

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
(1) EP 1079676	A3	20030827		
JP 3183653	B2	20010709		
US 6737588	B1	20040518	US 2000-640862	20000818 <
US 2002189857	A1	20021219	US 2002-230329	20020829
US 6729022	B2	20040504		
US 2003234085	A1	20031225	US 2003-423977	20030428

Abstract

The present invention aims to connect metal films without forming any opening in a resin film. Against a first resin film formed on a first metal film are pressed bumps on a second metal film so that the bumps are embedded into the first resin film. Either 1 of the first metal film or the second metal film or both is (are) patterned while the bumps are in contact with the first metal film, and the first resin film is heat-treated while the top of the first resin film is partially exposed to discharge the solvent or moisture from the exposed zone and cure the first resin film. After curing, the bumps and the first metal film may be ultrasonically bonded to each other. A second resin film and a third metal film may be further layered to form a multilayer structure.

Concept or Classification

76-3 (Electric Phenomena) Section cross-reference(s): 72

Supplementary Terms

manuf multilayer flexible wiring board

Controlled or Index Terms

Electrodeposition

(copper film; processes for manufacturing flexible wiring boards and resulting flexible wiring boards)

Etchina

Imidation

Interconnections (electric)

Multilayers

Photolithography

(processes for manufacturing flexible wiring boards and resulting flexible wiring boards)

Polyimides, uses

RL: DEV (Device component use); USES (Uses)

(resin **film**; processes for manufacturing flexible wiring boards and resulting flexible wiring boards)

7440-50-8 , **Copper** , processes

RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(metal film; processes for manufacturing flexible wiring boards and resulting flexible wiring boards)

STIC-EIC 2800

Jef4-A58

Scott Hertzog 571-272-2663

International Patent Classification

ICM H05K003-46

L19 ANSWER 5 OF 8 HCAPLUS COPYRIGHT 2004 ACS n STN

Accession Number

1984:143662 HCAPLUS Full Text

Document Number

100:143662

Title

Beryllium to metal seals

Author/Inventor

Bronnes, Robert L.; Sweet, Richard C.; O'Grady, James D.

Patent Assignee/Corporate Source

North American Philips Corp., USA

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 4431709	A	19840214	US 1982-427057	19820929 <
CA 1201679	A1	19860311	CA 1983-437319	19830922
JP 59082162	A2	19840512	JP 1983-176527	19830926

Abstract

The Be surface is **coated** with <u>3 layers</u> for reliable bonding to an alloy having a similar coefficient of thermal expansion. The 1st **layer** is a cathodically sputtered **film** (preferably 1000-5000 Å thick) of a refractory **metal** (Ta, Nb, Zr, Hf, Ti, or V). A 2nd **film** 4000-10,000 Å thick of refractory **metals** (especially Mo or W) is applied. The 3rd **film** 4000-10,000 Å thick is a brazeable **metal** (especially **Cu** or Ni). Brazing or **soldering** is then used for the joining. The method is suitable for Be **window foils**. Thus, circular Be **foil** .apprx.250 μ thick was degreased, dried, and **coated** on the edges by cathodic sputtering for successive **layers** of Ti 4500, Mo 8000, and Ni 5000 Å thick. The Be **foil** was then inserted into a cylindrical Kovar frame, and brazed in place with Ag-**Cu** alloy in H atmospheric at .apprx.780°. The resulting seal was suitable for vacuum tightness even when cycled between room temperature and 960°.

Concept or Classification

56-9 (Nonferrous Metals and Alloys)

Supplementary Terms

beryllium foil brazing coating; window x ray beryllium foil

Controlled or Index Terms

Sputtering

(films by, on beryllium foil for brazing)

X-ray tubes

(windows for, beryllium foil coating for

brazing for)

Soldering

(brazing, of beryllium foil , to alloy holders,

multilayer coatings for)

Windows

(x-ray, beryllium foil coating for brazing for)

7439-98-7, uses and miscellaneous 7440-02-0, uses and miscellaneous

7440-32-6, uses and miscellaneous

RL: USES (Uses)

(film , on beryllium foil , sputtered

multilayer coatings containing, brazing by)

7440-41-7, uses and miscellaneous

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RL: USES (Uses)
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(foil , brazing of, multilayer coatings

for)

National Patent Classification

428649000

International Patent Classification

C23C015-00

☐ L19 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2004 ACS on STN

Accession Number

1981:75636 HCAPLUS Full Text

Document Number

94:75636

Title

Printed circuits resistant to thermal shock effects

Author/Inventor

Paunovic, Milan

Patent Assignee/Corporate Source

Kollmorgen Technologies Corp., USA

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 3016132	A1	19801030	DE 1980-3016132	19800423
US 4303798	A	19811201	US 1979-34210	19790427 <
GB 2047974	A	19801203	GB 1980-13065	19800421
JP 55145397	A2	19801112	JP 1980-56112	19800424

Abstract

To increase the resistance of the through-hole metalization in a printed circuit to the effects of sudden heating, as during soldering, a 3-layer metalization is used, preferably Cu-Ni-Cu, in which the thermal expansions of the different metals compensate each other.

Concept or Classification

76-14 (Electric Phenomena)

Supplementary Terms

printed circuit hole metalization multilayer; copper nickel metalization circuit hole; thermal shock resistance printed circuit; expansion thermal printed circuit metalization

Controlled or Index Terms

Electric circuits

(printed, thermal-shock-resistant metalization for through

holes in)

Expansion, Dilation and Elongation

(thermal, of metal coatings on through

holes in printed circuits, compensation of)

7440-02-0, uses and miscellaneous 7440-50-8, uses and

miscellaneous

RL: USES (Uses)

(printed-circuit through hole multilayer

metalization containing, thermal shock-resistant)

7440-50-8 , uses and miscellaneous

RL: USES (Uses)

(printed-circuit through hole multilayer

metalization containing, thermal shock-resistant)

International Patent Classification

H05K003-42

L20 ANSWER 5 OF 16 HCAPLUS COPYRIGHT 2004 ACS IN STN

Accession Number

1996:88152 HCAPLUS Full Text

Document Number

124:161782

Title

Processes for manufacturing multilayer TAB

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
RD 373006		19950510		

Abstract

Several processes are disclosed for making multilayer tape automated bonding (TAB) for flexible circuits. These processes are simple compared to present methods and are more economical. The processes allow the fabrication of ground-plane two metal layer flexible circuits, screened ground-plane two metal layer flexible circuits, double-circuit two metal layer flexible circuits, plated ground plane two metal layer flexible circuits with through holes, three metal layer flexible circuits, and very fine-line multiple metal layer circuits.

Concept or Classification

76-3 (Electric Phenomena) Section cross-reference(s): 38, 56, 74

Supplementary Terms

fabrication *multilayer* TAB flexible circuit; polyimide flexible circuit Controlled or Index Terms

Electrodeposition and Electroplating

Etching

Soldering

Sputtering

(fabrication processes using **multilayer** TAB for flexible circuits)

Metals , processes

Polyimides, processes

RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)

(fabrication processes using **multilayer** TAB for flexible circuits)

Coating process

(screen; fabrication processes using **multilayer** TAB for flexible circuits)

Electric circuits

(flexible, fabrication processes using **multilayer** TAB for flexible circuits)

Electric conductors

(pastes, fabrication processes using **multilayer** TAB for flexible circuits)

Resists

(photo-, fabrication processes using **multilayer** TAB for flexible circuits)

Lithography

(photo-, UV, fabrication processes using multilayer TAB for flexible circuits)

1310-58-3, Potassium hydroxide, reactions

RL: RCT (Reactant); RACT (Reactant or reagent)

(chrome etchant and photoresist remover; fabrication processes using multilayer TAB for flexible circuits)

7722-64-7, Potassium permanganate

```
RL: RCT (Reactant); RACT (Reactant or reagent)
   (chrome etchant; fabrication processes using multilayer TAB
   for flexible circuits)
7440-47-3, Chromium, processes 7440-50-8, Copper,
processes
RL: DEV (Device component use); PEP (Physical, engineering or chemical
process); PROC (Process); USES (Uses)
   (fabrication processes using multilayer TAB for flexible
   circuits)
1310-73-2, Sodium hydroxide, reactions
RL: RCT (Reactant); RACT (Reactant or reagent)
   (photoresist remover; fabrication processes using multilayer
   TAB for flexible circuits)
7440-50-8 , Copper , processes
RL: DEV (Device component use); PEP (Physical, engineering or chemical
process); PROC (Process); USES (Uses)
   (fabrication processes using multilayer TAB for flexible
   circuits)
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L20 ANSWER 7 OF 16 HCAPLUS COPYRIGHT 2004 ACS on STN

Accession Number

1993:639843 HCAPLUS Full Text

Document Number

119:239843

Title

Printed circuit including copper -nickel-copper multilayer electric conductor and its manufacture

Author/Inventor

Ishibashi, Masao; Maniwa, Akira; Hirozawa, Koichi; Okada, Keisuke

Patent Assignee/Corporate Source

Nippon Electric Co, Japan

Patent Information

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05211386	A2	19930820	JP 1992-8887	19920122

Abstract

Claimed are (A) a printed circuit board having, successively deposited a Cu bottom layer, a Ni interlayer, and a Cu top layer, on an elec. insulating support optionally on the both sides and on inside wall of a through hole and (B) manufacture of the circuit by a process including following successive steps; (1) Ni coating on the whole surface of the both sides of a Cu -clad laminate, (2) selectively opening a through hole on the laminate, (3) Cu coating on the inside wall of the hole and the Ni layer, and (4) patterning the Cu-Ni-Cu layer or (C) manufacture of the circuit by a process including following successive steps; (1') selectively opening a hole on a Cu-clad laminate, (2') Cu - coating inside the hole to form a through hole, (3') patterning the Cu layer to from a circuit, (4') Ni coating on the inside wall of the through hole and the circuit, (5') forming a thick Cu film by electroless coating on the Ni layer, and (6') selectively coating a solder resist. The structure prevents diffusion of Sn to Cu layer in soldering.

Concept or Classification

76-14 (Electric Phenomena) Section cross-reference(s): 56

Supplementary Terms

copper clad laminate circuit board; nickel copper layered conductor circuit;
soldering resistance copper circuit board; tin diffusion prevention copper
circuit

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Controlled or Index Terms Electric conductors (copper -nickel-copper multlayer, for printed Soldering (resistance to, of printed circuit, copper -nickelcopper layered conductor for) Electric circuits (printed, prevention of diffusion of, in copper -nickelcopper layered conductors for) 7440-50-8 , Copper , uses RL: TEM (Technical or engineered material use); USES (Uses) (elec. conductor, associated with nickel interlayer, for printed circuit, prevention of tin diffusion during soldering in) 7440-02-0, Nickel, uses RL: TEM (Technical or engineered material use); USES (Uses) (interlayer film , for copper elec. conductor, for printed circuit, prevention of tin diffusion during soldering in) 7440-31-5, Tin, miscellaneous RL: PEP (Physical, engineering or chemical process); PROC (Process) (prevention of diffusion of, in copper -nickel-copper layered conductor, for printed circuit) **International Patent Classification** ICM H05K003-24 ICS H05K001-09; H05K003-18; H05K003-42

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FILE 'REGISTRY' ENTERED AT 09:47:09 ON 25 MAY 2004 L156875 S CU/MF, ELF AND NC=1 FILE 'HCAPLUS' ENTERED AT 09:47:13 ON 25 MAY 2004 L2 1108745 S L1 OR CU OR COPPER 2722578 S PATTERN? OR METAL? L3 120135 S BALL# OR BUMP? OR SOLDER? L4L5 2866 S BLM OR BALL(W)LIMIT? OR UBM OR UNDERBUMP? OR UNDER(W)BUMP? L6 1276350 S PLASMA? OR CLEAN#### OR IONIS? OR IONIZ? L7 758945 S WINDOW? OR ACCESS? OR HOLE? OR OPEN? L8QUE THIRD? OR 3 OR TERTIAR? OR THREE? QUE LAMEL? OR FILM? OR THINFILM? OR LAYER? OR OVERLAY? OR OVERLAID? L9 OR LAMIN? OR MULTI(W) LAYER? OR MULTILAYER? OR SHEET? OR LEAF? OR FOIL? OR COAT? OR TOPCOAT? OR OVERCOAT? OR VENEER? OR SHEATH? OR COVER? OR ENVELOP? OR ENCAS? OR ENWRAP? OR OVERSPREAD? OR LINING? OR LINER# 166 S L8 AND L9 AND L2 AND L3 AND (L4 OR L5) AND L7 L10 L1136 S H01L?/IC AND L10 0 S L11 NOT P/DT NOT PD>20011221 L12 L13 36 S L11 AND P/DT L14 6 S L13 AND (WO OR US)/AC(P)AD<20011221 20 S L13 NOT L14 NOT PD>20011221 L15 48 S L8(3A)L9 AND L10 L16 L17 5 S L16 NOT P/DT NOT PD>20011221 29 S L16 AND P/DT NOT L13 8 S L18 AND (WO OR US)/AC(P)AD<2 16 S L18 NOT L19 NOT PD>20011221 L18 L19 8 S L18 AND (WO OR US)/AC(P)AD<20011221 L20